

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Koichi NANIWAE

Conf.

Application No. **NEW NATIONAL PHASE**

Group

Filed March 24, 2006

Examiner

METHOD OF CLEANING TREATMENT AND METHOD FOR MANUFACTURING
SEMICONDUCTOR DEVICE**PRELIMINARY AMENDMENT**Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

March 24, 2006

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begin on page 3 of this paper.

Remarks begin on page 17 of this paper.

An **Appendix** is attached following the signature page of this paper.